

# Serie 11

## Given constants

$$\begin{aligned}kT/q &= 25.9 [mV] \quad @ \quad T = 300 [K] \\ n_i(Si) &= 1.5 \cdot 10^{10} [cm^{-3}] \quad @ \quad T = 300 [K] \\ q &= 1.60 \cdot 10^{-19} [C] \\ \epsilon_0 &= 8.85 \cdot 10^{-14} [F/cm] \\ \epsilon_{Si} &= 11.7 \cdot \epsilon_0 \\ \epsilon_{SiO} &= 3.9 \cdot \epsilon_0\end{aligned}$$

## Exercise 01

You have access to the specifications of an industrial CMOS technology that we want to consider for the design of an IC operating at  $T = 85 [^{\circ}C]$ . For a long-channel NMOS transistor, we have: an off current  $I_{off} = 1 [nA/\mu m]$ , a threshold voltage  $V_{th} = 0.5 [V]$ , a subthreshold slope  $SS = 70 [mV/dec]$ , all at  $T = 25 [^{\circ}C]$ . The current  $I_{off}$  is the current  $I_D$  at  $V_{GS} = 0 [V]$  and  $V_{DS} = V_{DD}$ , normalized by the channel width  $W$ . The subthreshold slope is defined as  $SS = \frac{\partial V_{GS}}{\partial (\log_{10} I_D)} = \ln(10) \cdot \frac{kT}{q} (1 + \frac{C_d}{C_{ox}})$  (in subthreshold, of course). The following formula holds:

$$I_D(V_{th}) = I_{off} \cdot 10^{\frac{V_{th}}{SS}}$$

Extract  $I_{off}$  at  $T = 85 [^{\circ}C]$ . Assume that the threshold voltage of your MOSFET changes with temperature according to  $\frac{dV_{th}}{dT} = -4 [mV/^{\circ}C]$ , over the range of interest for your application.

Hint: exploit the fact that the current  $I_D(V_{th})$  is defined constant, independently of  $V_{th}$ .

## Exercise 02

Consider the output characteristic  $I_D(V_D)$  (reported below) of a long-channel NMOS transistor, for the case where its body contact (B) is shorted with the source (S) to ground ( $0 [V]$ ). The channel length is  $L = 1 [\mu m]$  and the gate oxide thickness is  $t_{ox} = 10 [nm]$ . Answer the following questions:

- Assuming that the MOSFET has quasi-ideal long-channel transistor behavior, estimate its threshold voltage  $V_{th}$ .
- Estimate the electron mobility  $\mu_n$  of its inversion channel at low transverse field. How does this value compare with the volume electron mobility?

- Estimate its transconductance  $g_m$  at  $V_{GS} = 3[V]$  and  $V_{DS} = 3[V]$  for  $W = 10[\mu m]$ , under the same assumption of the first point. Comment on the possibility of choosing the transconductance value by design and compare it with the value of a bipolar transistor.
- Estimate the capacitance  $C_{GS}$  for the same  $V_{GS}$ ,  $V_{DS}$  and  $W$ . In saturation:  $C_{GS} \approx \frac{2}{3}WLC_{ox}$ .

